

L Number	Hits	Search Text	DB	Time stamp
86	10	((("5565084") or ("5811348") or ("5856229") or ("6376332") or ("6428620")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/19 17:31
87	25	((belt near2 like) same (ring or polygon)) same electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/19 17:34
88	1514	(belt near2 like) same electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/19 17:34
89	387	(anodize or anodizing) near substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/19 17:36
90	0	((belt near2 like) same electrode) and ((anodize or anodizing) near substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/19 17:36
91	4479	(first and second and third and fourth) near electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/19 17:37
92	3	((anodize or anodizing) near substrate) and ((first and second and third and fourth) near electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/19 17:37
-	226	((205/323) or (205/199)).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 16:28
-	13636	anodize or anodizing	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 16:29
-	49	((205/323) or (205/199)).CCLS.) and (anodize or anodizing)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 16:29
-	1348243	electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 16:32
-	31	((205/323) or (205/199)).CCLS.) and (anodize or anodizing) and electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 16:38
-	15	((("5856229") or ("5811348") or ("6190937") or ("6221738") or ("6382292") or ("6143628") or ("6306729") or ("6331208") or ("6613678") or ("6391743") or ("6211038") or ("6428620") or ("6376332") or ("5565084") or ("6258698")).PN.	USPAT	2004/03/18 16:41
-	3646500	apparatus	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 20:47

-	41465	electro near2 plating or electroless or electro near2 deposition	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 17:09
-	524	(anodize or anodizing) and (electro near2 plating or electroless or electro near2 deposition)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 17:09
-	244	((anodize or anodizing) and (electro near2 plating or electroless or electro near2 deposition)) and electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 17:09
-	658264	first and second and third and fourth	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 17:10
-	80	((anodize or anodizing) and (electro near2 plating or electroless or electro near2 deposition)) and electrode) and (first and second and third and fourth)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 17:11
-	60	apparatus and (((anodize or anodizing) and (electro near2 plating or electroless or electro near2 deposition)) and electrode) and (first and second and third and fourth))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 17:26
-	637	(anodize or anodizing) same apparatus	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 17:27
-	104298	(first and second and third and fourth) and electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 19:32
-	58	((anodize or anodizing) same apparatus) and ((first and second and third and fourth) and electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 19:29
-	138	((anodize or anodizing) same apparatus) same substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 19:31
-	387	(anodize or anodizing) near substrate	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 19:31
-	32230	(first and second and third and fourth) same electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 20:07
-	8	((anodize or anodizing) near substrate) and ((first and second and third and fourth) same electrode)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 19:33
-	1348243	electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 20:07

-	46	((anodize or anodizing) near substrate) same electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/19 17:35
-	30006	canon adj kabushiki adj kaisha	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 20:24
-	364	((anodize or anodizing) near substrate) not (canon adj kabushiki adj kaisha)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 20:24
-	3646500	apparatus	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 20:47
-	103	((anodize or anodizing) near substrate) not (canon adj kabushiki adj kaisha) and apparatus	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/18 20:47